

10/564510

1AP20 Rec'd PCT/PTO 12 JAN 2006

SHIGA7.036APC

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|----------------|---|---|
| Applicant | : | Masuda et al. |
| Appl. No. | : | Unknown |
| Filed | : | Herewith |
| For | : | POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN |
| Examiner | : | Unknown |
| Group Art Unit | : | Unknown |

PRELIMINARY AMENDMENT

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 5 of this paper.